## **ABSTRACT**

A pattern forming method is provided for forming line-shaped film patterns W1, W2 by arranging droplets of a liquid material on a substrate, wherein a plurality of pattern forming areas R1, R2 in which the film patterns should be formed are defined on the substrate, a first pattern forming area R1 formed from sides in a line-width direction of the film patterns and a second pattern forming area R2 formed from central portions in the line-width direction of the film patterns are defined from the plurality of pattern forming areas R1, R2, and the droplets are arranged in the first and second pattern forming areas R1, R2, thereby forming the film patterns W1, W2.